

Title (en)

APPARATUS AND METHOD FOR PLASMA TREATING AN ARTICLE

Title (de)

VORRICHTUNG UND VERFAHREN ZUR PLASMABEHANDLUNG EINES ARTIKELS

Title (fr)

APPAREIL ET PROCEDE DESTINE AU TRAITEMENT AU PLASMA D'UN ARTICLE

Publication

EP 1733411 A1 20061220 (EN)

Application

EP 04716162 A 20040301

Priority

US 2004006234 W 20040301

Abstract (en)

[origin: WO2005096345A1] The invention provides a plasma source (102) in which a gap (110) (i.e. cathode-to-anode distance) is adjustable in real time to a desired distance in response to selected conditions within a plasma chamber (104). At least one sensor (116) monitors and detects any change in such conditions within the plasma chamber (104). An apparatus (100) comprising at least one plasma source (102) generates at least one plasma that is stable and adjustable in real time. In one embodiment, the apparatus (100) includes multiple plasma sources (102) that can either be "tuned in real time to generate plasmas that are similar to each or, conversely, "detuned" to generate dissimilar plasmas. The apparatus (100) may be used to provide plasma treatment - such as, but not limited to, coating, etching and activation - for an article (160). Methods of providing such plasmas and treating an article (160) using such plasmas are also disclosed.

IPC 8 full level

H01J 37/32 (2006.01); **H05H 1/32** (2006.01); **H05H 1/34** (2006.01)

CPC (source: EP)

H01J 37/32055 (2013.01); **H01J 37/32357** (2013.01)

Citation (search report)

See references of WO 2005096345A1

Designated contracting state (EPC)

AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IT LI LU MC NL PL PT RO SE SI SK TR

DOCDB simple family (publication)

WO 2005096345 A1 20051013; EP 1733411 A1 20061220

DOCDB simple family (application)

US 2004006234 W 20040301; EP 04716162 A 20040301